

UNITED STATES PATENT AND TRADEMARK OFFICE

BEFORE THE PATENT TRIAL AND APPEAL BOARD

SAMSUNG ELECTRONICS CO., LTD., AND
SAMSUNG ELECTRONICS AMERICA, INC.
Petitioner

v.

SINOTECHNIX LLC.
Patent Owner

Case No. IPR2025-00332
U.S. Patent No. 7,951,626

PETITIONER'S UPDATED EXHIBIT LIST

PETITIONER’S EXHIBIT LIST

Petitioner Exhibit No.	DESCRIPTION
1001	U.S. Patent No. 7,951,626 (“’626 Patent”)
1002	Declaration of Dr. Ioannis Kymissis
1003	PCT Application Publication No. WO2002/059983 (“Eliashevich”)
1004	U.S. Patent No. 5,378,309 (“Rabinzohn”)
1005	U.S. Patent Application Publication No. 2003/0189212 (“Yoo”)
1006	U.S. Patent No. 6,444,410 (“Huang”)
1007	U.S. Patent Application Publication No. 2005/0281303 (“Horio”)
1008	U.S. Patent Application Publication No. 2006/0169993 (“Fan”)
1009	U.S. Patent No. 7,053,419 (“Camras”)
1010	U.S. Patent No. 6,229,160 (“Krames”)
1011	H. Xiao, “Introduction to Semiconductor Manufacturing Technology,” “Chapter 6,” Prentice Hall, 2001
1012	File History of U.S. Patent No. 7,951,626
1013	File History of U.S. Application No. 11/993,965
1014	L.F. Thompson, “Introduction to Microlithography,” “Chapter 1. Introduction to Photolithography,” <i>ACS Symposium Series</i> Vol. 219, 1983 (“Thompson”) ¹
1015	D. J. Kim, “Characterization and Modeling of Positive Photoresist,” Memorandum No. UCB/ERL M84/65, 1984 (“Kim”)
1016	S. L. Morton et al., “Ultrasonic Sensor for Photoresist Process Monitoring,” <i>IEEE Transactions on Semiconductor Manufacturing</i> , Vol. 12, No. 3, August 1999 (“Morton”)
1017	E. J. Jewell et al., “The New Oxford American Dictionary,” Oxford University Press, p. 1286, 2001
1018	Docket Control Order in <i>Sinotechnix LLC v. Samsung Electronics et al.</i> , 2:24-cv-544-JRG-RSP
1019	Judicial Caseload For Eastern District of Texas
1020	Judge Gilstrap’s Case Schedule (May 4, 2026)
1021	T. Nakazawa et al., “Compact and monolithic coarse wavelength-

¹ Available at <https://pubs.acs.org/doi/10.1021/bk-1983-0219.ch001>

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	division multiplexer-demultiplexer fabricated by use of a high-spatial-frequency transmission grating buried in a slab waveguide,” Vol. 29, Issue 11, pp. 1188-1190, 2004 (“Nakazawa”) ²
1022	U.S. Patent Application No. 2006/0231852 (“Kususe”)
1023	H. Jansen et al., “A survey on the reactive ion etching of silicon in microtechnology,” Micromechanics Europe 1995 Technical Digest, 1995 (“Jansen”)
1024	<i>Sotera</i> Stipulation

All annotations, coloring, and emphases have been added unless indicated otherwise.

Dated: April 21, 2025

Respectfully submitted,

/Yung-Hoon Ha/

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² Available at <https://opg.optica.org/ol/abstract.cfm?uri=ol-29-11-1188>.

CERTIFICATE OF SERVICE

The undersigned certifies that on April 21, 2025, complete a copy of the foregoing **Petitioner's Updated Table of Exhibits and corresponding exhibit (Sotera Stipulation)** was served on counsel of record for the Patent Owner by filing the documents through P-TACTS and by sending via electronic mail to the following addresses:

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